Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	303	(438/723.ccls. or 438/719.ccls. or 438/745.ccls. or 438/753.ccls. or 438/756.ccls. or 438/757.ccls.) and ((form$5 or generat$3 or produc$3 or mak$3 or manufactur$3 or creat$3 or fabricat$3) with (via or hole$1 or opening$1)) and (glass with (wafer$1 or substrate$1))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:35
L2	74377	((form$5 or generat$3 or produc$3 or mak$3 or manufactur$3 or creat$3 or fabricat$3) with (via or hole$1 or opening$1)) and (glass with (wafer$1 or substrate$1))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:37
L3	185	L2 and polysilicon and (sandblast$3 or (sand adj blast$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:37
L4	78	L3 and ((wet adj3 etch$3) or (etch$3 near3 solution) or (etch$3 adj3 bath) or (liquid adj3 etch$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:37
L5	76	L3 and (polysilicon same glass)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:39
L6	303	L1 not L4 not L5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:38
L7	60	L1 and (polysilicon same glass)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/14 16:39